L	Hits	Search lext	DB	Time stamp
Number		"mothy!	USPAT;	2002/11/10
2	31	ammonia or "NH.sub.3" same methyl fluoride" or "CH.sub.3F"	EPO; JPO; IBM TDB	12:13
			USPAT;	2002/11/10
3	12	(ammonia or "NH.sub.3") and ("methyl		12:13
		fluoride" or "CH.sub.3F") and etch\$5	EPO; JPO;	1
			IBM_TDB	2302/11/10
;	9952	ammonia or "NH.sub.3") same etch\$5	USPAT;	2002/11/10
7			EPO; JPO;	11:56
			IBM_TDB	
r	. 2	ammonia or "NH.sub.3"; same etch\$5;	USPAT;	2:02/11/10
5	- 4-	same "low k"	EPO; JPO;	12:02
		Jame 100 ii	IBM TDB	
ė.	4.6	ammonia or "NH.sub.3", same etch\$5	USPĀT:	2002/11/10
r	2.2	and "low k"	EPO: JPO:	12:03
		and low h	IBM TDB	
		Wattr - who 2 th came throughthy	USPAT;	2002/11/10
ਰ	154	<pre></pre>	EPO; JPO;	12:38
		fluoride" or "CHF. sub. 3"); and econs	IBM TDB	12.07
				:2002/11/10
9	5	("CF.sub.4" or CF4 or "carbon		13:59
		tetrafluoromethane") same		13.37
		("C.sub.4F.sub.8" or C4F8 or	IBM_TDB	
		octofluorocyclobutane) same (oxygen or		
		"0.sub.2")	uanam.	2002/11/10
10	21	("CF.sub.4" or CF4 or "carbon	USPAT;	13:19
		tetrafluoromethane") and	EPO; JPO;	13.19
		("C.sub.4F.sub.8" or C4F8 or	IBM_TDB	
		octofluorocyclobutane) and (oxygen or		
		"O.sub.2")	· HODDT.	2002/11/10
7	23€	ammcnia or "NH.sub.3") same ("methyl	USPAT;	13:13
		fluoride" or "CHF.sub.3")	EPO; JPO;	13.13
			IBM_TDB USPAT;	2002/11/10
11	7170	("silicon oxide" or SiO) same organic	EPO; JPO;	
				13.14
			IBM_TDB	2002/11/10
12	78	("silicon oxide" or SiO) same "organic	USPAT;	2002/11/10
		dielectric"	EPO; JPO;	13:17
			IBM_TDB	5000/11/10
13	9985	(parylene or polyether or polyimide) same	USPAT;	2002/11/10
1 -7		etch\$5	EPO; JPO;	13:20
			IBM_TDB	
14	956	"CF.sub.4" or CF4 or "carbon	USPAT;	2002/11/10
17	,,,,	retrafluoromethane") and ((parylene or	EPO; JPO;	13:19
		nolvether or nolvimide) same etch\$5)	IBM_TDB	
16	76	(parylene or polyether or polyimide) same	USPAT;	2002/11/10
1.0		etch\$5 same fluorocarbons	FFO; OFO;	13:27
		C C C C C C C C C C C C C C C C C C C	IBM_TDB	
17	1	6080529.pn.	USPAT;	2002/11/10
1 /	*	00000251	EPO; JPO;	13:27
			IBM_TDB	*
13	196	"low k" same etch\$5	USPAT:	2002/11/10
13	100	1011	EPO: JPO:	13:42
			IBM_TDB	
1.5		"CF.sub.4" or CF4 or "carbon	USPĀT;	2002/11/10
19	<u>.</u>	tetrafluoromethane") same	EPO; JPO;	13:59
		"C.sub.4F.sub.8" or C4F8 or	IBM_TDB	
		octofluorocyclobutane) same "low k"	=	
22.0	2.1	("CF.sub.4" or CF4 or "carbon	USPAT;	2002/11/10
20	2.1	tetrafluoromethane") and	EPO; JPO;	14:07
		("C.sub.4F.sub.8" or C4F8 or	IBM TDB	
		octofluorocyclobutane) and (oxygen or	-	
		"0.sub.2")		
	V =1			